

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| | | |
|----------------|---|---|
| Applicant | : | Hirayama et al. |
| Appl. No. | : | 10/590,046 |
| Filed | : | June 15, 2007 |
| For: | : | BASE MATERIAL FOR PATTERN-FORMING MATERIAL, POSITIVE RESIST COMPOSITION AND METHOD OF RESIST PATTERN FORMATION |
| Examiner | : | Johnson, C. |
| Group Art Unit | : | 1795 |

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **April 24, 2009**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 8 of this paper.